

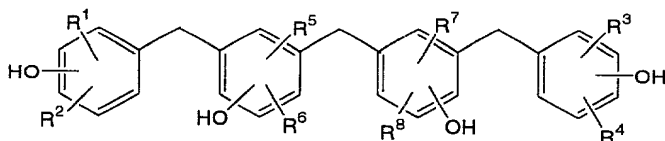
WHAT IS CLAIMED IS:

1. A positive photoresist composition comprising:

(A) an alkali-soluble resin;

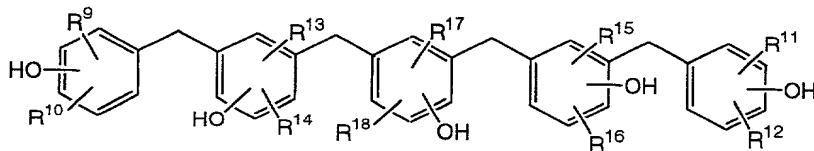
(B) a photosensitizer comprising a quinonediazide ester between a naphthoquinonediazidosulfonic acid compound and at least one of a compound represented by following Formula

(I):



(I)

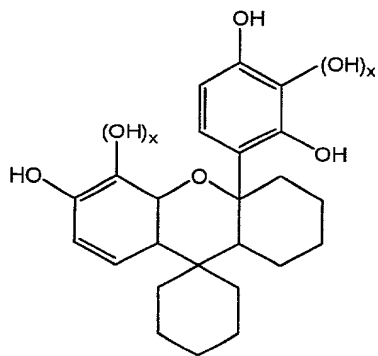
wherein R¹, R², R³, R⁴, R⁵, R⁶, R⁷ and R⁸ are each independently a hydrogen atom or an alkyl group having from 1 to 3 carbon atoms, and a compound represented by following Formula (II):



(II)

wherein R^9 , R^{10} , R^{11} , R^{12} , R^{13} , R^{14} , R^{15} , R^{16} , R^{17} and R^{18} are each independently a hydrogen atom, an alkyl group having from 1 to 3 carbon atoms or a cyclohexyl group; and

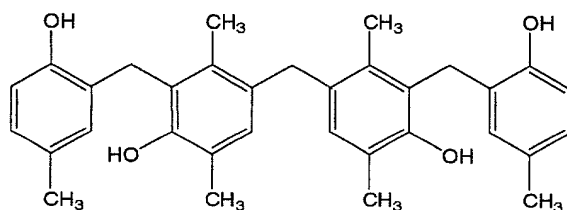
(C) a sensitizer comprising at least one of compounds represented by following Formula (III):



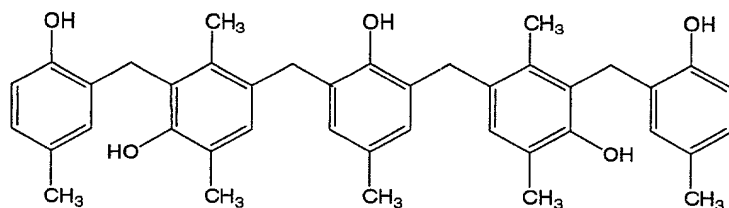
(III)

wherein x is 0 or 1.

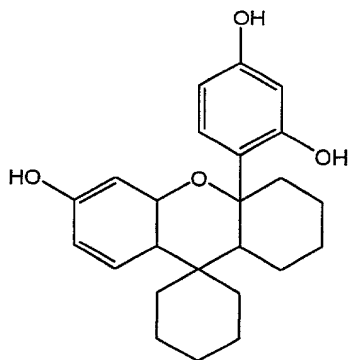
2. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (I) is a compound represented by the following formula:



3. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (II) is a compound represented by the following formula:



4. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:



5. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:

